NEK-150-SC

Products

- RHEED
- AUGER / XPS / EELS / REELS
- Electron Sources
  - General Purpose Electron Sources
  - Microfocus and Nanofocus Electron Sources
  - Electron Flood Sources
  - High Beam Power Electron Sources
  - High Energy Small Focus Electron Sources
  - Low Energy Electron Sources
    - NEK-150
    - **NEK-150-SC**
    - F01CC
  - Electron Sources for RHEED

This electron source provides a high beam current at low beam energies as needed for dissociation, ionization, excitation, and charge neutralization. This model has scanning capability.

Key features

- Energy range 1 eV – 100 eV
- Beam current (max.) 100 µA
- Beam size (min.) 2 mm at max energy and 21 mm working distance

Characteristics

- Working Distance (WD) 15 mm – 50 mm
- Optimum WD 21 mm nominal
- Basic beam blanking (optional)
- Computer control (optional)
- Magnetic shielding (optional)
- Beam scanning (optional)
- Remote control

Not all parameters can be reached simultaneously. Above specifications may change without notice. Pictures / diagrams for reference only.

Typical Applications

Control of chemical reactions and synthesis by low-energy electrons

Neutralization

Desorption

Dissociation

Related Products

Filaments

Complete service kit w/o filament

Diagnostic box

AES and XPS energy spectrometers (ESA and DESA)

- Accessories for Electron Sources
- Ion Sources
- X-ray Source
- Energy Analyzers & Imaging Energy Filters
- Charged Particle Detectors
- PEEM & IEEM
- UHV-Systems for Surface Analysis
- Packages for Surface Analysis
- Data Acquisition & Instrument Control Software

Ionization of gases

Secondary Electron Detectors (SED) for imaging

Faraday cups

Sample current measurement kit

Gun control module

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APPLICATIONS

- *In situ* Characterization
- Surface Analysis Techniques
- Material Growth Monitoring
- Electron Diffraction
- Scanning Electron Microscopy
- Photoelectron Microscopy (PEEM)
- Depth Profiling
- Space Environment Simulation
- Surface & Materials Modification

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